

Guowang Li

List of Publications by Year in descending order

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31
papers

1,419
citations

430874
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610901
24
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32
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32
docs citations

32
times ranked

1297
citing authors

#	ARTICLE	IF	CITATIONS
1	Strained GaN quantum-well FETs on single crystal bulk AlN substrates. <i>Applied Physics Letters</i> , 2017, 110, .	3.3	48
2	High-voltage polarization-induced vertical heterostructure p-n junction diodes on bulk GaN substrates. , 2015, , .	3	
3	Dual optical marker Raman characterization of strained GaN-channels on AlN using AlN/GaN/AlN quantum wells and ^{15}N isotopes. <i>Applied Physics Letters</i> , 2015, 106, .	3.3	13
4	Two-dimensional electron gases in strained quantum wells for AlN/GaN/AlN double heterostructure field-effect transistors on AlN. <i>Applied Physics Letters</i> , 2014, 104, .	3.3	42
5	Polarization-Induced GaN-on-Insulator E/D Mode p-Channel Heterostructure FETs. <i>IEEE Electron Device Letters</i> , 2013, 34, 852-854.	3.9	55
6	Time delay analysis in high speed gate-recessed E-mode InAlN HEMTs. <i>Solid-State Electronics</i> , 2013, 80, 67-71.	1.4	7
7	Ultrascaled InAlN/GaN High Electron Mobility Transistors with Cutoff Frequency of 400 GHz. <i>Japanese Journal of Applied Physics</i> , 2013, 52, 08JN14.	1.5	66
8	InGaN Channel High-Electron-Mobility Transistors with InAlGaN Barrier and $f_T > 260/220$ GHz. <i>Applied Physics Express</i> , 2013, 6, 016503.	2.4	35
9	Quaternary Barrier InAlGaN HEMTs With f_T/f_{max} of 230/300 GHz. <i>IEEE Electron Device Letters</i> , 2013, 34, 378-380.	3.9	58
10	Ultra-thin Body GaN-on-insulator nFETs and pFETs: Towards III-nitride complementary logic. , 2012, , .	7	
11	InAlN/AlN/GaN HEMTs With Regrown Ohmic Contacts and f_T of 370 GHz. <i>IEEE Electron Device Letters</i> , 2012, 33, 988-990.	3.9	292
12	Ultra-low resistance ohmic contacts to GaN with high Si doping concentrations grown by molecular beam epitaxy. <i>Applied Physics Letters</i> , 2012, 101, , .	3.3	42
13	MBE-Regrown Ohmics in InAlN HEMTs With a Regrowth Interface Resistance of 0.05 Ω/mm . <i>IEEE Electron Device Letters</i> , 2012, 33, 525-527.	3.9	118
14	Ultrathin Body GaN-on-Insulator Quantum Well FETs With Regrown Ohmic Contacts. <i>IEEE Electron Device Letters</i> , 2012, 33, 661-663.	3.9	40
15	Effect of optical phonon scattering on the performance limits of ultrafast GaN transistors. , 2011, , .	2	
16	Presence and origin of interface charges at atomic-layer deposited Al ₂ O ₃ /III-nitride heterojunctions. <i>Applied Physics Letters</i> , 2011, 99, .	3.3	140
17	Barrier height, interface charge & tunneling effective mass in ALD Al ₂ O ₃ /AlN/GaN HEMTs. , 2011, , .	3	
18	Comparative study of E- and D-mode InAlN/AlN/GaN HEMTs with f_T near 200 GHz. , 2011, , .	1	

#	ARTICLE	IF	CITATIONS
19	210-GHz InAlN/GaN HEMTs With Dielectric-Free Passivation. <i>IEEE Electron Device Letters</i> , 2011, 32, 892-894.	3.9	88
20	220-GHz Quaternary Barrier InAlGaN/AlN/GaN HEMTs. <i>IEEE Electron Device Letters</i> , 2011, 32, 1215-1217.	3.9	71
21	Si-Containing Recessed Ohmic Contacts and 210 GHz Quaternary Barrier InAlGaN High-Electron-Mobility Transistors. <i>Applied Physics Express</i> , 2011, 4, 096502.	2.4	10
22	MBE growth of high conductivity single and multiple AlN/GaN heterojunctions. <i>Journal of Crystal Growth</i> , 2011, 323, 529-533.	1.5	45
23	Metalâ€face InAlN/AlN/GaN high electron mobility transistors with regrown ohmic contacts by molecular beam epitaxy. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2011, 208, 1617-1619.	1.8	25
24	Subcritical barrier AlN/GaN E/D-mode HFETs and inverters. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2011, 208, 1620-1622.	1.8	16
25	Polarizationâ€engineering in group IIIâ€nitride heterostructures: New opportunities for device design. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2011, 208, 1511-1516.	1.8	83
26	High mobility two-dimensional electron gases in nitride heterostructures with high Al composition AlGaN alloy barriers. <i>Applied Physics Letters</i> , 2010, 97, .	3.3	14
27	Threshold Voltage Control in \$hbox{Al}_{\{0.72\}} hbox{Ga}_{\{0.28\}}hbox{N/AlN/GaN}\$\$ HEMTs by Work-Function Engineering. <i>IEEE Electron Device Letters</i> , 2010, 31, 954-956.	3.9	47
28	Quantum transport in graphene nanoribbons patterned by metal masks. <i>Applied Physics Letters</i> , 2010, 96, .	3.3	45
29	High performance E-mode InAlN/GaN HEMTs: Interface states from subthreshold slopes. , 2010, , .	1	
30	Work-function engineering in novel high Al composition Al<inf>0.72</inf>Ga<inf>0.28</inf>N/AlN/GaN HEMTs. , 2010, , .	0	
31	Quantum transport in patterned graphene nanoribbons. , 2009, , .	1	